



partnering for process control

You are cordially invited to attend the following talks involving Nova technology and customer collaboration:

## SPIE. **ADVANCED LITHOGRAPHY**

### CONFERENCE 10145 Metrology, Inspection, and Process Control for Microlithography XXXI

- February  
**27**  
Monday
- Electrical test prediction using hybrid metrology and machine learning [10145-3]**  
Speaker: Mary Breton, IBM Corp. (USA)  
**1:40 PM SESSION 2** (Hybrid Metrology)
- February  
**27**  
Monday
- Hybrid scatterometry measurement for BEOL process control [10145-5]**  
Speaker: Pdraig R. Timoney, GLOBALFOUNDRIES (USA)  
**2:20 PM SESSION 2** (Hybrid Metrology)
- March  
**1**  
Wednesday
- Complex metrology on 3D structures using multi-channel OCD [10145-48]**  
Speaker: Taher Kagalwala, GLOBALFOUNDRIES (USA)  
**4:00 PM SESSION 11** (Optical Metrology)
- March  
**1**  
Wednesday
- Scatterometry control for multiple electron-beam lithography [10145-51]**  
Speaker: Yoann Blancquaert, CEA-LETI (France)  
**5:00 PM SESSION 11** (Optical Metrology)
- March  
**1**  
Wednesday
- Advanced optical modeling of TiN metal hard mask for scatterometric critical dimension metrology [10145-52]**  
Speaker: Carsten Hartig, GLOBALFOUNDRIES Dresden Module One LLC & Co. KG (Germany)  
**5:20 PM SESSION 11** (Optical Metrology)
- March  
**2**  
Thursday
- Materials characterization for process integration of multi-channel gate all around (GAA) devices [10145-66]**  
Speaker: Raja Muthinti, IBM Corp. (USA)  
**3:30 PM SESSION 15** (Late Breaking News)
- March  
**2**  
Thursday
- Application of advanced hybrid metrology method to nanoimprint lithography [10145-108]**  
Speaker: Ilya Osherov, Nova Measuring Instruments Ltd. (Israel)  
**4:50 PM SESSION 15** (Late Breaking News)

### SHORT COURSE

- February  
**26**  
Sunday
- Scatterometry in Profile, Overlay and Focus Process Control [SC1100]**  
Instructors: Hugo Cramer, ASML Netherlands B.V. (Netherlands);  
Igor Turovets, Nova Measuring Instruments Ltd. (Israel)  
**1:30 PM - 5:30 PM**

For more information visit the official SPIE Advanced Lithography website:  
<http://spie.org/conferences-and-exhibitions/advanced-lithography/conferences>